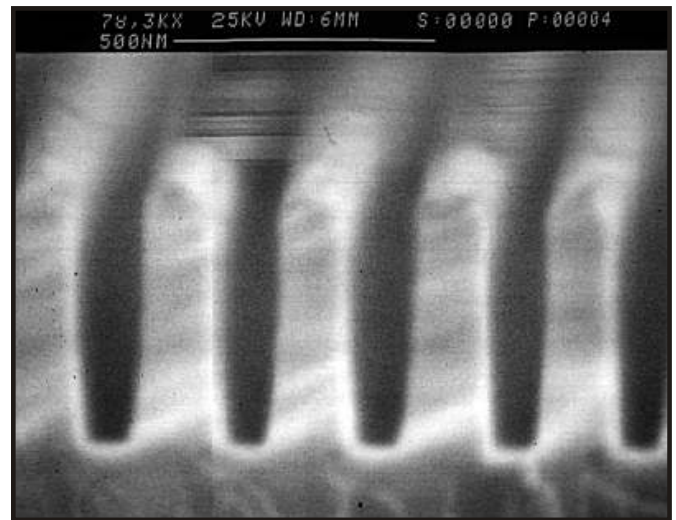
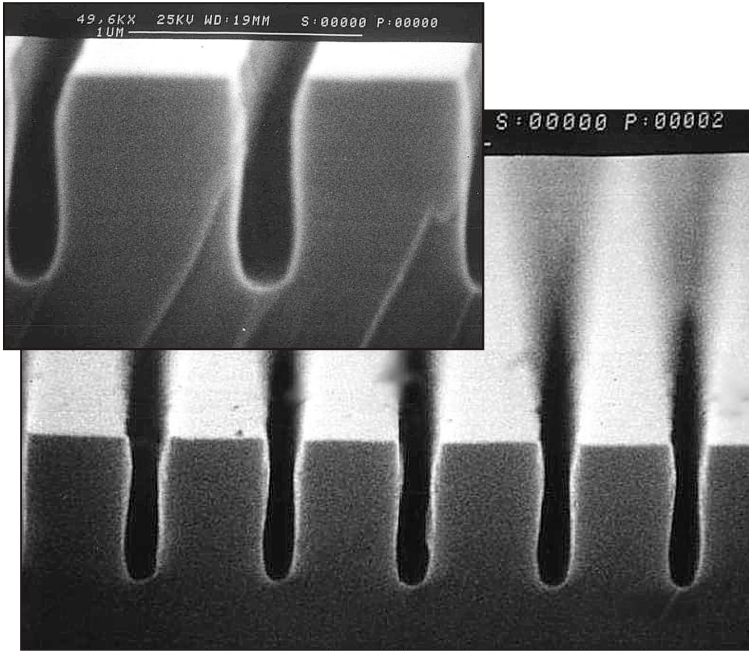
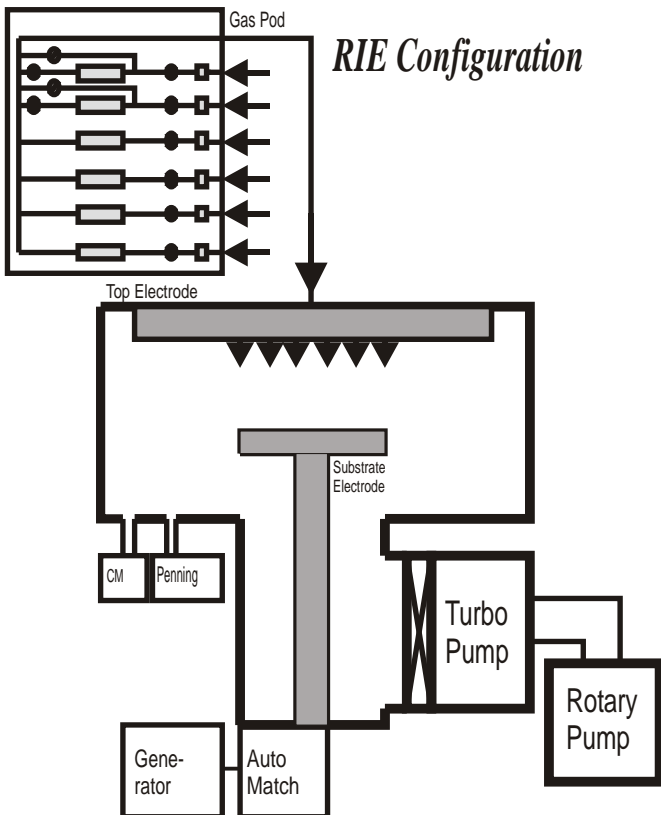


# Plasmalab Data

## Anisotropic Quartz RIE



0.3 / 0.15  $\mu$ m wide, 1 / 0.6  $\mu$ m deep etches  
OPT application lab, Yatton (UK)



*RIE Configuration*

- Plasmalab 80 Plus*
- Plasmalab 800 Plus*
- Plasmalab System 100*
- Plasmalab System 133*



**Technology:**  
13.56 MHz Plasma  
Fluorine based Process  
Parallel Plate Reactor  
Shower Head Gas Inlet

**Results:**  
Uniformity:  $\leq \pm 4\%$   
Rate: ca 50 nm/min  
Selectivity to Cr:  $> 30 : 1$  (Ni  $> 80 : 1$ )  
Anisotropic process  
Excellent linewidth control